

FORM PTO-1449
(Rev. 12-32)U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.
SMA-001SERIAL NO.
09/425,494INFORMATION DISCLOSURE
STATEMENT BY APPLICANTAPPLICANT
REDDY

(USE SEVERAL SHEETS IF NECESSARY)

FILING DATE
10/22/99GROUP
2811

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROP.
K.N.	A	4,786,907	Nov. 22, 1988	Koelle	342	51	Jul. 14, 1986
K.N.	B	4,816,839	Mar. 28, 1989	Landt	343	795	Dec. 18, 1987
K.N.	C	4,877,641	Oct. 31, 1989	Dory	427	38	May 31, 1988
K.N.	D	4,910,499	Mar. 20, 1990	Benge, et al.	340	572	Feb. 10, 1989
K.N.	E	5,346,850	Sep. 13, 1994	Kaschmitter, et al.	437	81	Oct. 29, 1992
K.N.	F	5,444,223	Aug. 22, 1995	Blama	235	435	Jan. 11, 1994
K.N.	G	5,528,222	Jun. 18, 1996	Moskowitz, et al.	340	572	Sep. 9, 1994
K.N.	H	5,572,226	Nov. 5, 1996	Tuttle	343	726	Apr. 11, 1995
K.N.	I	5,708,419	Jan. 13, 1998	Isaacson, et al.	340	572	Jul. 22, 1996
K.N.	J	5,779,839	Jul. 14, 1998	Tuttle, et al.	156	213	Sep. 26, 1997

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	PUB. DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	K							
	L							
	M							
	N							

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER INITIAL		
K.N.	O	"1994 Display Manufacturing Technology Conference Digest of Technical Papers", Society for Information Display, First Edition, January, 1994, 16 pages.
K.N.	P	"1994 Seminar Lecture Notes", Society for Information Display, Volume I: June 13, 1994, Figures 1-44, 23 pages.
K.N.	Q	"1995 Display Manufacturing Technology Conference Digest of Technical Papers", Society for Information Display, First Edition, January, 1995, 16 pages.
K.N.	R	"An Amorphous Silicon Thin Film Transistor Fabricated at 125°C by DC Reactive Magnetron Sputtering", C.S. McCormick, et al., Appl. Phys. Lett. 70 (2), 13 January 1997, 1997 American Institute of Physics.
K.N.	S	"Low Temperature Fabrication of Amorphous Silicon Thin Film Transistors by DC Reactive Magnetron Sputtering", C.S. McCormick, et al., J. Vac. Sci. Technol. A 15(5), Sep/Oct 1997, 1997 American Vacuum Society.

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DATE CONSIDERED

Khiem Nguyen

12/20/02

EXAMINER: Initial of citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



SHEET 2 OF 2

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U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROP.
KN	A	5,786,626	Jul. 28, 1998	Brady, et al.	257	673	Mar. 25, 1996
KN	B	5,796,121	Aug. 18, 1998	Gates	257	59	Mar. 25, 1997
KN	C	5,817,550	Oct. 6, 1998	Carey, et al.	438	166	Mar. 5, 1996
KN	D	5,856,858	Jan. 5, 1999	Carey, et al.	349	158	Dec. 1, 1997
KN	E	5,912,632	Jun. 15, 1999	Dieska, et al.	340	825.54	Jan. 8, 1997
KN	F	5,929,760	Jul. 27, 1999	Monahan	340	572.7	Oct. 20, 1997
	G						
	H						
	I						
	J						

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	PUB. DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	K							
	L							
	M							
	N							

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER INITIAL		
KN	O	"Chapter 3, Manufacturing and Infrastructure of Active Matrix Liquid Crystal Displays", Malcolm Thompson, 12/10/97.
KN	P	"PolySilicon Thin Film Transistors Fabricated at 100°C on a Flexible Plastic Substrate", YIJ. Tung, et al.,
KN	Q	"RFID: Card Manufacturing Fundamentals", Michael L. Davis, 10/11/99, 53 pages of slides.
KN	R	"Computer Display Industry and Technology Profile", Display Industry and Technology Profile, 7/28/99, 59 pages.
KN	S	

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